



INFORMATION DISCLOSURE CITATION PTO-1449	Atty. Docket No. NTI-025	Serial No. 10/025,414
	Applicant TSAI, Chi-Ming	
	Filing Date 12/18/2001	Group 2123

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
JSP	5,974,243	10/26/1999	Moh, et al.	395	500.03	10/31/1997
JSP	6,045,584	4/4/2000	Benzel, et al.	716	11	10/31/1997
JSP	6,077,307	6/20/2000	Benzel, et al.	716	2	10/31/1997

RECEIVED
DEC 12 2002
Technology Center 2100

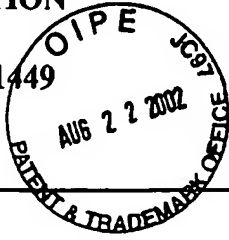
EXAMINER:

Date Considered:

2/23/2005

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE CITATION PTO-1449	Atty. Docket No. NTI-025	Serial No. 10/025,414-4802
	Applicant TSAI, Chi-Ming	Group 2123
Filing Date 12/18/2001	RECEIVED AUG 26 2002 Technology Center 2100	



U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
Jal	5,801,954	9/1/1998	Le, et al.	364	488	4/24/1996
Jal	6,081,659	6/27/2000	Garza, et al.	395	500.22	4/26/1999

EXAMINER: _____

Date Considered: _____

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

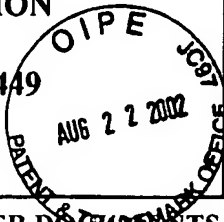


INFORMATION DISCLOSURE CITATION PTO-1449		Atty. Docket No. NTI-025		Serial No. 10/025,414-4802			
		Applicant TSAI, Chi-Ming		Group 2123			
Filing Date 12/18/2001		RECEIVED AUG 26 2002 Technology Center 2100					
FOREIGN PATENT DOCUMENTS							
EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
JSP	WO 00/67075 A1	11/9/2000	WO			<input type="checkbox"/>	<input type="checkbox"/>
JSP	WO 00/67076 A1	11/9/2000	WO			<input type="checkbox"/>	<input type="checkbox"/>
JSP	WO 99/14638 A1	3/25/1999	WO			<input type="checkbox"/>	<input type="checkbox"/>

EXAMINER:

Date Considered:

2/23/2005

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

INFORMATION DISCLOSURE CITATION PTO-1449 		Atty. Docket No. NTI-025 Applicant TSAI, Chi-Ming Filing Date 12/18/2001	Serial No. 10/025,414-4802 RECEIVED AUG 26 2002 Group 2123 Technology Center 2100
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)			
EXAMINER'S INITIALS	CITATION		
	Cai, L., et al., "Enhanced Dispositioning of Reticle Defects Using the Virtual Stepper with Automated Defect Severity Scoring", Numerical Technologies, Inc., Advanced Micro Devices, Inc., pp. 1-12.		
	Ronse, K., et al., "Thin Film Interference Effects in Phase Shifting Masks Causing Phase and Transmittance Errors", IMEC (15 pages).		
	Casey, Jr., J.D., et al., "Chemically Enhanced FIB Repair of Opaque Defects on Molybdenum Silicide Photomasks", SPIE, Vol. 3236, pp. 487-497 (1997).		
	Henke, W., et al., "A Study of Reticle Defects Imaged Into Three-Dimensional Developed Profiles of Positive Photoresist Using the Solid Lithography Simulator", Microelectronics Eng., Vol. 14, pp. 283-297 (1991).		
	Ham, Y.M., et al., "Dependence of Defects in Optical Lithography", Jpn. J. Appl. Phys., Vol. 31, pp. 4137-4142 (1992).		
	Watanabe, H., et al., "Detection and Printability of Shifter Defects in Phase-Shifting Masks II Defocus Characteristics", Jpn. J. Appl. Phys., Vol. 31, pp. 4155-4160 (1992).		
	Nistler, J., et al., "Phase Shift Mask Defect Printability Analysis", Proceedings Of The Microlithography Seminar INTERFACE '93. OCG Microelectronic Materials, Inc., pp. 11-28 (1993).		
	Spence, C., et al., "Automated Determination of CAD Layout Failures Through Focus: Experiment and Simulation", SPIE, Vol. 2197, pp. 302-313 (1994).		
	Karklin, L., "A Comprehensive Simulation Study of the Photomask Defects Printability", SPIE, Vol. 2621, pp. 490-504 (1995).		
	Gans, F., et al., "Printability and Repair Techniques for DUV Photomasks", SPIE, Proceedings Of The 17th Annual Symposium On Photomask Technology And Management, Vol. 3236, pp. 136-141 (1997).		
	Ibsen, K., et al., "Clear Field Reticle Defect Disposition for Advanced Sub-Half Micron Lithography", SPIE, Proceedings Of The 17th Annual Symposium On Photomask Technology And Management, Vol. 3236, pp. 124-135 (1997).		
	Tsujiimoto, E., et al., "Hierarchical Mask Data Design System (PROPHET) for Aerial Image Simulation, Automatic Phase-Shifter Placement, and Subpeak Overlap Checking", SPIE, Vol. 3096, pp. 163-172 (1997).		
	Gordon, R., et al., "Design and Analysis of Manufacturable Alternating Phase-Shifting Masks", Bacus News, Vol. 14, Issue 12, pp. 1-9, December 1998.		
	Chen, et al., "ArF (193nm) Alternating PSM Quartz Defect Repair and Printability for 100nm Node", BACUS Photomask Technology, September 21, 2001 (20 pages).		

EXAMINER:

Date Considered:

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.